

FORM PTO-49

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
MICRON.137DV2C1APPLICATION NO.
10/719,501

FEB 20 2004

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

(USE SEVERAL SHEETS IF NECESSARY)

APPLICANT
Ahn, et al.FILING DATE
November 21, 2003GROUP
2832

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
Am	1	3,881,244	05/06/75	Kendall			
	2	3,918,148	11/11/75	Magdo et al.			
	3	3,988,764	10/26/76	Cline, et al.			
	4	5,062,197	11/05/91	Charles			
	5	5,098,528	03/24/92	DeLalande, et al.			
	6	5,227,659	07/13/93	Hubbard			
	7	5,329,020	02/21/95	Chang			
	8	5,569,626	10/29/96	Kurtz et al.			
	9	5,781,091	7/14/98	Krone et al.			
	10	5,831,331	11/03/98	Lee			
	11	5,852,866	12/29/98	Kuettner			
	12	5,861,647	01/19/99	Zhao, et al.			
	13	5,863,024	01/26/99	Blind, et al.			
	14	5,896,078	04/20/99	Hayakawa et al.			
	15	5,898,020	04/27/99	Goyal et al.			
	16	5,949,030	09/07/99	Fasano et al.			
	17	6,168,422	12/26/00	Qian et al.			
Am	18	6,249,039	06/19/01	Harvey et al.			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
Am	19	05198440	08/1993	JP				

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
Am	20	MacChesney, et al. "Chemical Vapor Deposition of Iron Oxide Films for Use as Semitransparent Masks." Journal of the Electrochemical Society. May, 1971. pp. 776-781.
Am	21	Shigematsu, et al. "Magnetic Properties of Amorphous Iron (III) Oxide Thin Films." Journal de Physique. March, 1979. pp. C2-153-154.
Am	22	Domke, et al. "Magnetic and Electronic Properties of Thin Iron Oxide Films." Surface Science. August, 1982. pp. 727-732.

EXAMINER	Am	DATE CONSIDERED	June 3, 04
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.			

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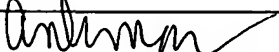
EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
Am	23	Ouchi, et al. "High Rate Deposition of Iron-Oxide Thin Film by Reactive Sputtering." IEEE Transactions on Magnetics. September, 1983. pp. 1980-1982.
	24	Kaito, et al. "Structure of Iron Oxide Films Prepared by Evaporating Various Iron Oxide Powders." Applications of Surface Science. October, 1984. pp. 621-630.
	25	Lin, et al. "Properties of RF Sputtered Iron Oxide Thin Films with CoCr and Nb as Dopants." IEEE Transactions on Magnetics. September, 1985. pp. 1462-1464.
	26	Joshi, et al. "Pulsed Laser Deposition of Iron Oxide and Ferrite Films." Journal of Applied Physics. November, 1988. pp. 5647-5649.
	27	Li, et al. "Preparation of Amorphous Iron-containing and Crystalline Iron Oxide Films by Glow Discharge and Their Properties." Materials Science and Engineering. 1990. pp. 5-13.
	28	Dubin, Valery M. "Formation Mechanism of Porous Silicon Layers Obtained by Anodization of Monocrystalline N-type Silicon in HF Solutions." Surface Science. February, 1992. pp. 82-92.
	29	Dhara, et al. "Direct Deposition of Highly Coercive Gamma Iron Oxide Thin Films for Magnetic Recording." Journal of Applied Physics. December, 1993. pp. 7019-7021.
	30	Fujii, et al. "Low-Temperature Preparation and Properties of Spinel-Type Iron Oxide Films by ECR Plasma-Enhanced Metalorganic Chemical Vapor Deposition." Japanese Journal of Applied Physics. October, 1993. pp. L1527-L1529.
	31	Seki, et al. "Pressure/Photo Sensor Utilizing Polymer Magnetic Composite." IEEE Transactions on Magnetics. November, 1993. pp. 3189-3191.
	32	Gokturk, et al. "Electric and Magnetic Properties of a Thermoplastic Elastomer Incorporated with Ferromagnetic Powders." IEEE Transactions on Magnetics. November, 1993. pp. 4170-4176.
	33	Nedkov, et al. "Microwave Polymer-Ferroxide Film Absorbers." IEEE Transactions on Magnetics. November, 1994. pp. 4545-4547.
	34	Itoh, et al. "Ferrite Plating of Ba-Containing Iron Oxide Films Using Chelated Highly Alkaline (pH=11-13) Aqueous Solutions." Japanese Journal of Applied Physics. March, 1995. pp. 1534-1538.
	35	Craciun, et al. "On the Morphology of Porous Silicon Layers Obtained by Electrochemical Method." 1995 International Semiconductor Conference Proceedings. October, 1995. pp. 331-334.
	36	Lagorce, et al. "Micromachined Polymer Magnets." IEEE Abstract. 1996. pp 85-90.
	37	Hong, et al. "Granular Magnetic Cobalt Metal/Polymer Thin Film System." IEEE Transactions on Magnetics. September, 1996. pp. 4475-4477.
	38	Savin, et al. "Properties of Laser Ablated Porous Silicon." Applied Physics Letter. November, 1996. pp. 3048-3050.
	39	Wan, et al. "A Composite of Polyaniline with Both Conducting and Ferromagnetic Functions." Journal of Polymer Science. 1997. pp. 2129-2136.
	40	Vadera, et al. "Preparation and Study of Finely Dispersed Magnetic Oxide in Polymer Matrix." Journal de Physique IV. March, 1997. pp. C1-549-C1-550.
	41	Kim, et al. "Surface Micromachined Solenoid Inductors for High Frequency Applications." 1997 International Symposium on Microelectronics Proceedings. pp. 1-8.
	42	Ouyang, et al. "Structure and Magnetic Properties of Iron Oxide Films Deposited by Excimer Laser Ablation of a Metal-Containing Polymer." Materials Research Bulletin. 1997. pp. 1099-1107.
	43	Baba, et al. "Ferromagnetic Particle Composite Polymer Films for Glass and Semiconductor Substrates." Optics Communications. June, 1997. pp. 35-38.
	44	Liu, et al. "Layer-by-Layer electrostatic Self-assembly of Nanoscale Fe ₃ O ₄ Particles and Polyimide Precursor on Silicon and Silica Surfaces." Applied Physics Letter. October, 1997. pp. 2265-2267.
	45	Nam, et al. "High-Performance Planar Inductor on Thick Oxidized Porous Silicon (OPS) Substrate." IEEE Microwave and Guided Wave Letters. August, 1997. pp. 236-238.
	46	Park, et al. "Ferrite-based Integrated Planar Inductors and Transformers Fabricated at Low Temperature." IEEE Transactions on Magnetics. September, 1997. pp. 3322-3324.
	47	Soh, et al. "Ultra-low Resistance, Through-Wafer VIA (TWV) Technology and Its Applications in Three Dimensional Structures on Silicon." 1998 International Conference on Solid State Devices and Materials Proceedings. pp. 284-285..
Am	48	Park, et al. "Fully Integrated Micromachined Inductors with Electroplated Anisotropic Magnet Cores." 1998 Applied Power Electronics Conference and Exposition Proceedings. pp. 379-385.

EXAMINER <i>Anderson</i>	DATE CONSIDERED <i>June 9, 04</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.	

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Am	49	Namkung, et al. "Effects of Heat Treatment on the Magnetic Properties of Polymer-bound Iron Particle Cores." Journal of Applied Physics. June, 1998. pp. 8474-8476.
Am	50	Dimitrov, et al. "Stoichiometry and Magnetic Properties of Iron Oxide Films." 1997 Fall MRS Symposium Proceedings. pp. 89-94.
Am	51	Ahn, A Fully Integrated Planar Toroidal Inductor with a Micromachined Nickel-Iron Magnetic Bar, 09/1994, IEEE Transactions on Components, Packaging, and Manufacturing Technology, Part A, Vol. 17 pages 463-469.

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EXAMINER 	DATE CONSIDERED June 4, 04
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